

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An LPCVD apparatus comprising, a container for accommodating an organometallic compound, said compound serving as a raw material; a heating means for heating the container and vaporizing the organometallic compound to obtain a raw material gas; a reactor for accommodating a substrate on which a thin film is precipitated; an exhaust pump for maintaining a low pressure atmosphere within the reactor; and a trap provided on the upstream of the exhaust pump and cooling used raw material gas supplied from the reactor, wherein said trap is provided with metal honeycomb-structure cylindrical fillers in a flowing passage through which the used raw material flows.
2. (Original) The LPCVD apparatus according to claim 1, wherein the length of the honeycomb-structure cylindrical fillers is in a range of 0.01 to 1.0 m in a direction along which the used raw material flows.
3. (Previously Presented) The LPCVD apparatus according to claim 1, wherein the honeycomb-structure cylindrical fillers have holes with a maximum diameter of 0.5 to 10.
4. (Previously Presented) The LPCVD apparatus according to claim 1, wherein said apparatus is provided with a trap-pressure-regulating valve for adjusting the internal pressure in the trap, and the exhaust pump.

5. (Previously Presented) The LPCVD apparatus according to claim 1, wherein said apparatus is provided with a back-flow valve for preventing a back flow of the used raw material in the trap, said back-flow valve being located between the reactor and the trap.
6. (Previously Presented) The LPCVD apparatus according to claim 1, wherein said apparatus is connected with a first and a second pipes and provided with a by-pass pipe which bypasses the trap, said first pipe connecting the reactor and the trap and said second pipe connecting the trap and the pump.
7. (Previously Presented) The LPCVD apparatus according to claim 1, wherein said by-pass pipe is provided at the both ends thereof with a back-flow valve.
8. (Withdrawn) A method of manufacturing a thin film with the use of the LPCVD apparatus, said apparatus defined in claim 1, wherein an internal pressure in the trap is kept equal to or lower than that in the reactor.
9. (Cancelled).